



PATENT
Atty. Dkt. No.: AMAT/5619 DSM/LOW KJW

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:
Nguyen, et al.

Serial No.: 09/912,103

Confirmation No.: 4476

Filed: July 23, 2001

For: Selective Etching of Organosilicate
Films Over Silicon Oxide Stop Etch
Layers

Assistant Commissioner of Patents
Washington, D.C. 20231

Dear Sir:

**PROPOSED CORRECTION TO THE DRAWINGS
AND SUBMISSION OF FORMAL DRAWINGS**

Applicant proposes correction of the drawings for reasons discussed below.

IN THE DRAWINGS

Applicants propose correction of the drawings to submit a page of formal drawings that were inadvertently not filed with the patent application. The submitted page of formal drawings includes figures 4f and 4g that were inadvertently omitted from the original figures as filed. Figures 4f and 4g conform to the written description of the invention without adding new matter.

REMARKS

Applicants respectfully submit that the submitted proposed page of formal drawings does not introduce new matter or removes helpful description of the invention. Approval of the amendments is respectfully requested.

Further, please find 6 sheets of formal drawings as attached, including the page of formal drawings including figures 4f and 4g, with gummed labels identifying the application for which they are submitted. The Examiner is requested to substitute these formal drawings for the drawings originally submitted when filing the subject patent application.

Any comparison fee should be charged to Deposit Account No. 20-0782/AMAT/5619/DSM/LOW K/KMT. Two copies of this document are enclosed for your convenience. If any additional informalities are identified by the Examiner, please contact the undersigned attorney at (713) 623-4844.

Respectfully submitted,



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